of application of the accelerated stress influences the life of a product.

The technique of accelerated life testing incorporates the selection of accelerated stress and acceleration level, test procedure design such as multiple level acceleration or step stress acceleration, and test data extrapolation including physical model determination and statistical inference model selection.

TYPES OF ACCELERATED TESTING

The accelerated life tests can be classified into constant stress test, step stress test, progressive stress test, cyclic stress test, and random stress test based on the pattern of applied stresses.

Constant Stress Test

LIFE TESTING The constant stress life test is a most common accelerated Modern electronic products demonstrate very high reliability
when is used by many standard test methods such as
when operated in their intended normal usage environment.
Therefore, it is difficult to perform a reliability

ucts subject to manufacturing and process changes. That it is easy to maintain the test conditions and easy to The accelerated life tests have been conducted in many ap- perform the test data analysis. The inference models for the

around during development of new products or mature prod- Two advantages of the constant accelerated life test are

plications such as failure mode examination, endurance/dura- constant stress test are well developed and empirically veribility investigation, environmental stress screening, and re- fied, and there are historical data of similar products for comliability improvement/growth management. Failure mode parison. examination tests attempt to identify the main failure modes and site of a system under certain environmental conditions. **Step Stress Test** Endurance/durability tests are used to provide reasonable assurance that life requirement will be met. Accelerated envi- In the step stress test, specimens are tested initially at an ronmental stress screening is an approach to remove causes operational stress level but after a certain holding time the of the early failure resulting from defects due to inadequate stress level is increased step wise to different levels for the manufacturing and assembly processes. Accelerated reliabil- same holding times until failure. Usually all specimens go ity improvement/growth tests are used to achieve ultimate through the same specified stress pattern. Sometimes differreliability goals by improving the design or manufacture ent stress patterns are applied to different specimens. Figure based on the information obtained from the tests.

The objective of accelerated life testing is to estimate mean time to failure, failure rate, and life distribution of the products and extrapolate the results to normal usage condition. Since the interest is to obtain absolute value of the life, the applied stress should be based on the operating stress in-service mission profile. Although the data obtained from these tests can be treated in a relative manner, the product failures in these tests must be associated with failure that could arise under field use conditions. It is very important to identify the failure mechanism and elevate the accelerated stress only to the extent that the failure mechanism is not changed. In accelerated life test design and test data interpretation, it is always necessary to understand what acceleration model will be used for a particular failure mechanism, how it is influenced by the nature of the testing, and how varying the rate **Figure 1.** Constant stress acceleration.

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circles. Compared to the constant stress test, step stress test- **Random Stress Test** ing reduces test time and assures that failure occurs quickly. This assurance comes from correctly selecting the stress level Some products in operation undergo randomly changing lev-
els of stress as depicted in Fig. 5. For example, airplane com-

engineers often fail to note. The reliability inference model to cally employs random stress with the same distribution as
account for the effect is usually very complicated. The step actual random stress but at high level account for the effect is usually very complicated. The step actual random stress but at high levels. Like cyclic stress
stress tests are therefore often carried out as comparisons for tests, random stress models employ so stress tests are therefore often carried out as comparisons for tests, random stress models employ some characteristics of products with different designs and manufacture, or as pre-
the stress distribution, such as root m products with different designs and manufacture, or as pre-
liminary activity before more complex and expensive constant
nower spectral density (PSD). In Fig. 5 the irregularity of the stress tests. Compared to constant stress tests, the step stress tests generate a life test more quickly. However, these data might be less precise due to the simplified hypotheses that each step is not influenced by previous ones.

Step stress testing is often performed with temperature acceleration. The stress steps between various temperatures are around 25C. The step stress tests are relatively easy to accomplish and do not require many samples.

Progressive Stress Test

In the progressive stress test, a specimen undergoes a continuously increasing level of stress. Different groups of specimens may undergo progressive stresses at different rates. Figure 3 depicts such a test with two linear increasing stress rates. Usually, specimens tend to have a longer lifetime before failure at a lower stress rate. Compared to constant stress acceleration, the progressive stress test is difficult to perform, especially in accurately controlling the applied stresses.

Figure 3. Progressive stress acceleration. **Figure 4.** Cyclic stress acceleration.

Cyclic Stress Test

Many products repeatedly undergo cyclic stress due to environmental temperature change, device power cycles, mechanical vibration, dc voltage, and so on. A cyclic stress test for a product repeatedly loads a specimen with the same stress pattern at a high level of the stress range, a high level of mean stress, or a high frequency, as shown in Fig. 4. For most products, the stress cycle is sinusoidal. If the mean stress is always zero, the accelerated stress can be characterized by the level of stress range or stress amplitude, as shown by Fig. Time 4(a). For the purpose of modeling and data analysis, such cy-Figure 2. Step stress acceleration. **Figure 2.** Step stress acceleration. **Fig. 1, where the vertical axis should be the stress range** or stress amplitude. A cyclic stress can also be accelerated by 2 depicts two stress patterns with the failure data repre-
sented by Fig. 4(b,c). $\frac{1}{2}$ and $\frac{1}{2}$ increasing the level of the mean stress or frequency, as shown
by Fig. 4(b,c).

els of stress, as depicted in Fig. 5. For example, airplane com-The failure mechanism at high stress levels may be differ-
ent from the one at lower stress levels, and this is something
systems undergo random vibration. An accelerated test typisystems undergo random vibration. An accelerated test typipower spectral density (PSD). In Fig. 5 the irregularity of the

random stress can be represented by the bandwidth of the must be careful because the damage model may be valid only

In accelerated life tests, there are two ways to terminate the ent model. test: time-terminated tests and failure-terminated tests. Time-terminated tests are terminated after a predefined **ACCELERATED STRESSES** number of test clock-hours T_o , have elapsed. The number of failed components during the test time, n_f , and the corre-
spanding time to failure of each component are recorded At causes or is the predominant cause of the time-dependent fail-
spanding time to failure of each compo are met, since the test duration is set in advance. However, tablished. Since the precision of the hazard function depends on the number of failures and not on the number of total com-**Accelerated Temperature** ponents being tested, a bad choice of sample size or test condi-

Failure-terminated tests are terminated when a predefined chemical reactions. Because the failure mechanisms of many number of component failures, n_f , have occurred. The time to electronic products are basically physica failure of each failed component and the time, T_{n_f} , that the last failure occurred are recorded. This procedure has an advantage in guaranteeing adequate data. However, the length be modeled by the Arrhenius model: of test time is random and open-ended.

The degree of stress acceleration in an accelerated life test is usually expressed by an acceleration factor (AF), which is defined as the ratio of the mean time to failure (MTTF) under where E_A is the activation energy for the failure mechanism
normal use conditions. MTTF, and that under the accelery under consideration, k is Boltzmann's co

$$
AF = \frac{MTTF_n}{MTTF_a} \tag{1}
$$

The acceleration factor can be calculated from a damage scale. model that gives a functional relationship between MTTF and The Arrhenius model should be used when only one failure

PSD diagram. The stress values and may not apply the stress values and may not apply outside these limits. One should keep in mind that a shift in **Termination of Accelerated Tests** *Termination of Accelerated Tests Termination of Accelerated Tests*

sponding time to failure of each component are recorded. At causes or is the predominant cause of the time-dependent fail-
the end of the test there are $n - n_c$ survivors, where n is the ure is selected as the accelerated the end of the test there are $n - n_f$ survivors, where *n* is the ure is selected as the accelerated stress. Accelerated stresses total number of tested products. All that is known about the can include thermal stress, suc total number of tested products. All that is known about the can include thermal stress, such as temperature, temperature survivors is that the times of failure are beyond $T_{\rm w}$. The time-cycles, or rate of temperate c survivors is that the times of failure are beyond T_o . The time-
terminated test has the advantage of ensuring that schedules humidity, corrosives, acid, or salt; electrical stress, such as terminated test has the advantage of ensuring that schedules humidity, corrosives, acid, or salt; electrical stress, such as vi-
are met, since the test duration is set in advance. However, voltage, current, or power; and as a random quantity, the number of total failures is not es-
tablished Since the precision of the hazard function depends most commonly used accelerated stresses are discussed next.

tions may result in insufficient information. Temperature is known to vary the rates of many physical and
Failure-terminated tests are terminated when a predefined chemical reactions. Because the failure mechanisms of many electronic products are basically physical/chemical processes, temperature is often used as the acceleration stress in life testing. The life dependence of a product on temperature can

$$
\ln(MTTF) = \ln(A) + (E_{\Lambda}/k)(1/T) \tag{2}
$$

normal use conditions, MTTF_n, and that under the acceler-
eV/K), and T is the absolute temperature. Equation (2) illus-
eV/K), and T is the absolute temperature. Equation (2) illusated condition, MTTF_a: eV/K), and *T* is the absolute temperature. Equation (2) illus-
trates that the natural logarithm of time to failure varies lin- $AF = \frac{MTTF_n}{MTTF_n}$ (1) early with the inverse of the absolute temperature for a given mechanism. Figure 6 shows a plot of the inverse of junction temperature versus the time to failure of a device on a log

accelerated stress. In calculating the acceleration factor, one mechanism occurs, so that E_A has a constant value that char-

Figure 6. Accelerated temperature.

acterizes the failure mechanism. As shown in Fig. 6, the acti- where T_n and T_a are the temperatures in a normal usage envi-
vation energy can be obtained by drawing a line from the ref- ronment and under accelerated t erence point E parallel to the curve obtained. The intercept of this line (dashed line in Fig. 6) on the right-hand side scale gives the activation energy of the failure mechanism. Table 1 **Accelerated Humidity**

$$
AF = \exp\left[\frac{E_A}{k}\left(\frac{1}{T_n} - \frac{1}{T_a}\right)\right]
$$
 (3)

ronment and under accelerated test conditions, respectively.

lists activation energies for various failure mechanisms. The failure mechanisms affected by humidity include corro-The acceleration factor for the Arrhenius reaction rate sion of metallization, electrolytic conduction between electri-
cally biased metallization paths and charge senaration on the cally biased metallization paths, and charge separation on the surface of metal oxide semiconductor (MOS) structures. In plastic encapsulated devices, the failure related to moisture absorption results mainly from corrosion of the aluminum

Table 1. Activation Energies for Various Failure Mechanisms of Silicon Devices

Sensitive Element	Failure Mechanism	Relevant Factors ^a	Accelerating Stress^a	Typical Activation Energy
Dielectric and interfaces Si	Accumulation of surface charges	T, E/V	T, V	$1.0-1.05$ eV (leakage-type failures)
dielectric	Breakdown	T, E/V	E, T	$0.3-0.6$ eV $(0.36$ eV for MOS gate structures)
	Oxide pinholes	T, E/V	E, T	1.0 eV (dielectric breakdown of bi- polar devices)
	Ionic contamination	T	т	1.0 eV
	Hot carrier trapping in oxide	E/V , T	E, T	-0.06 eV
	Charge loss	E, T	E, T	0.8 eV (MOS)
Metallization	Electromigration	T, J	T, J	1.0 eV (large grain Al, glassivated)
		Grain size		0.5 eV (small grain Al)
				0.7 eV (small grain Cu-Al)
	Contact electromigration	T, J	T, J	
	Si in Al			0.9 eV
	Al at sidewalls			$0.8 - 1.4$ eV
	Contact metal migration through barrier laver	T	т	1.8 eV
	Corrosion	Contamination	H, E/V, T	$0.3 - 0.7$ eV (Al)
	Chemical			$0.6-0.7$ eV (for electrolysis)
	Galvanic			0.65 eV (for corrosion mechanism)
	Electrolytic			E/V may have thresholds
Metal interfaces	Intermetallic compounds (Au, Al)	T, impurities, bond strength	T	1.0 eV (for open wires or high-re- sistance bonds at the pad bond due to Au-Al intermetallics)
Wafer fabrication and	Metal scratches	T, V	T, V	$0.5 - 0.7$ eV
assembly-related defects				0.7 eV for assembly-related defects

 a H = humidity, V = voltage, E = electric field, T = temperature, J = current density.

metallization. The chemical reaction of aluminum with hy- The failure mechanisms of electrolytic conduction between droxyl and hydrogen ions, produced by the electrolysis of wa- electrically biased metallization paths were also observed in ter aided by the applied bias, leads to the formation of alumi- accelerated humidity tests. The rate of transfer of metal from num hydroxide and alumina. This finally results in failure one electrode to another, across a conductive surface, will dedue to an open circuit. The corrosion mechanism is acceler- pend on (among other things) the electrolytic current flow. ated by condensed moisture, temperature, and the applied The conductivity of the surface is a function of the amount of bias. Although application of forward bias results in an in- moisture on the surface. The degree of metal transfer shows crease in the junction temperature, it does not accelerate the up as a leakage current (and eventually a short) resulting corrosion mechanism because increased temperature due to from a developing metal–metal compound film in the transfer
operation of a device at a rated current inhibits the condensa- path. The time required for failure will operation of a device at a rated current inhibits the condensation of moisture inside the package (a prerequisite for corro- tivity of the circuit to interpath leakage, the spacing between sion). In the reverse bias state, moisture can condense but metal traces, the applied voltage, the metals involved, and adequate temperature acceleration is not provided.

When the temperature is kept as a constant, the acceleration factor due to humidity acceleration is often expressed as **Accelerated Voltage**

$$
AF = \exp\left[E_H \left(\frac{1}{RH_n} - \frac{1}{RH_a}\right)\right]
$$
 (4)

are the relative humidity values under accelerated and field an electronic product is subjected to a high voltage, there is use conditions, respectively. There are several other models an increased tendency for failures related to accumulation of for accelerated humidity testing. All include the effect of rela- surface charge, dielectric breakdown, dendritic growth, elective humidity and temperature. trical overstress, and ionic contamination. In most cases, tests

bias conditions to ensure that localized heating does not cause would be observed. The rate of galvanic corrosion also dea reduction in relative humidity. The THB test is often car- pends on the voltage difference across two metals in contact ried out at 85 C and 85% relative humidity with the device when the device is biased. This voltage difference may get operating under reverse bias conditions. Because of low cur- superimposed on the already existing electrochemical potenage retains a high level of humidity. The THB (85/85) test reaction significantly. usually requires a thousand hours of testing time. In order to The failure rate for a device depends on both the collector reduce the test time, the highly accelerated stress test base voltage, V_{ch} , and the junction te reduce the test time, the highly accelerated stress test (HAST) was developed to apply high temperatures $(100^{\circ}\text{C to}$ monly used models for accelerated voltage tests are the Eyr-175C) at controlled humidity levels (relative humidity of 50% ing model and the Kemeny model, which relate failure rate, to 85%) and electrical bias as stress factors. λ , of the device to the device junction temperature, T_i , and the

to moisture absorption, resulting in the corrosion of the alu- pressed as follows: minum metallization. The chemical reaction of aluminum with hydroxyl and hydrogen ions, produced by the electrolysis of water aided by the applied bias, leads to the formation of aluminum hydroxide and alumina. This finally results in an open circuit (failure). Thus the corrosion mechanism is accel-
erated by both water vapor and the applied bias. The applica-
tion of forward bias, however, results in an increase in the
junction temperature, which causes moisture.

The failure mechanism of charge separation on the surface of MOS structures was observed. Moisture on the surface of field effect devices provides mobility to insulator surface charges, extending the gate potential over the nearby sur-
faces is the activation energy, $V_{cb,m}$ is the maximum allow-
faces. In certain structures, or with processing defects, para-
able collector base voltage, and $C_$ faces. In certain structures, or with processing defects, para-
sitic gates become operable, causing malfunction of the prod-
first part of the above relationships describes the dependence uct. This effect will occur as soon as sufficient humidity and of failure rate, λ , on the junction temperature, T_i . The second suitable fields are available. \blacksquare exponential term represents the dependence of λ on applied

Voltage, in conjunction with temperature, is an agent of many surface degradation processes. At low power dissipation, the voltage-activated failure mechanisms of the cellular diode dominate, while at high temperatures, failure of the emitter where E_H is a humidity activation energy, and RH_a and RH_a diode caused by thermal runaway becomes significant. When Galvanic corrosion cannot be accelerated significantly by have to be performed at voltages not much higher than those humidity because it depends on the flow of electrons across used under normal operating conditions, because device metals of different electrochemical potentials in contact. breakdown voltages are not very much higher than normal operating voltage. High electric fields increase the mobility of any contaminating ions that may be present. This effectively **Accelerated Cyclic Temperature/Humidity/Bias** changes the relative proportion of majority and minority car-The temperature, humidity, and bias (THB) test uses reverse riers and deviation from designed performance parameters rent, the power dissipated by the device is low and the pack- tial difference between the metals and may alter the rate of

Failures of plastic encapsulated devices are often related applied collector base voltage, V_{cb} . The Eyring model is ex-

$$
\lambda = AT_j \left[\exp\left(\frac{-B}{kT_j}\right) \right] \left[\exp\left(CV_{\rm cb} + \frac{DV_{\rm cb}}{kT_j}\right) \right]
$$
(5)

$$
\lambda = \left[\exp\left(C_0 - \frac{E_{\rm A}}{kT_{\rm j}} \right) \right] \left[\exp\left(C_1 \frac{V_{\rm cb}}{V_{\rm cb,m}} \right) \right] \tag{6}
$$

first part of the above relationships describes the dependence

voltage, V_{cb} . In fact, if V_{cb} is set equal to zero, the Kemeny model reduces to the Arrhenius equation. The value of the constant C_1 has been found to be 1.5. This value is valid for low to medium-voltage devices, up to $V_{cb} = 60$ V. For highervoltage devices, C_1 should be chosen between 1.5 and 2.305, depending on the voltage rating of the product. Having determined C_1 for a failure mechanism with known activation energy, the Kemeny model can be used to find C_0 by conducting a single life test. The upper junction temperature limit to be used was 200°C to 230°C for germanium devices and beyond 300° C for silicon planar devices. Above these limits, atypical failure mechanisms occurred, defeating the purpose of accel-Failure mechanisms occurred, defeating the purpose of accel-
erated tests.
Mean cycles to failure, log *N*

Keeping temperature as a constant, the acceleration factor can be derived to be **Figure 7.** Stress–life curve (*S-N* curve).

$$
AF = \left(\frac{V_a}{V_n}\right)^m \tag{7}
$$

cling or vibration. For high-cycle fatigue, material behaviors the failure mechanism under service conditions. present the following relationship between applied stress range and fatigue life: **Accelerated Random Vibration Accelerated Random Vibration**

$$
N = C\sigma_{\rm r}^m \tag{8}
$$

mechanical stress range, and *C* and *m* are fatigue constants The main application of PSD acceleration is for stress screento be determined from accelerated testing. For low-cycle fa- ing and qualification tests. The addition of random vibration tigue, the following equation was proposed to predict the ther- to a ''burn-in'' program greatly speeds screening and reduces

$$
N = \frac{1}{2} \left(\frac{\epsilon_r}{2\epsilon_f} \right)^b \tag{9}
$$

tility coefficient and exponent. As for material properties, these constants should be determined by accelerated testing. fatigue reliability prediction because many electronic prod-Figure 7 shows that both Equations (8) and (9) give straight ucts are installed on ships, automobiles, and aerospace vehilines on a strain-versus-cycle diagram with a logarithmic cles, where the operational environments tend to be random scale. In accelerated fatigue tests, the stress or strain range in nature. was elevated by accelerating the mechanical loading cycles or the thermal cycles. An acceleration of stress range in testing Under a random vibration environment, the dominant momay shift the failure mechanism from high-cycle fatigue to tions are due to the fundamental resonant mode, and the low-cycle fatigue. Therefore the prediction of fatigue life stress cycles associated with these dominant motions at a failbased on linear extrapolation of accelerated test data (dotted ure site are directly proportional to the square root of the PSD line in Fig. 7) may give an overly conservative prediction if at the resonant frequency. In general, the value of the PSD the stress range is accelerated only to a certain level. function is not explicitly related to the fatigue life as the

Accelerated Frequency

where V_a and V_n are voltages under accelerated and normal Frequency increase is usually a good accelerated test method
use conditions, respectively, and m is a constant. factor to be achieved is not very large. Since frequency is not Accelerated Mechanical Stress **Acceleration parameter**, the acceleration of frequency generally will not induce the failure mechanism to shift. How-Electronic components are required to withstand both con-
stant and cyclic mechanical stresses. In many electronic sys-
ture or a corrosive environment, frequency acceleration may ture or a corrosive environment, frequency acceleration may tems, the alternating stress induced by both thermal cycling also shift the failure mechanism because failure will be sensiand mechanical vibration is a dominant stress, and the fail-
ure mechanisms of greatest significance are those related to ment, and fatigue damage will be mixed with creen damage ure mechanisms of greatest significance are those related to ment, and fatigue damage will be mixed with creep damage
cumulative fatigue damage. Most of the failures start from at high temperatures. For example in a solder cumulative fatigue damage. Most of the failures start from at high temperatures. For example, in a solder joint fatigue
defects and flaws that vary from gross drilled-hole misalign-
test, the high frequency acceleration ma defects and flaws that vary from gross drilled-hole misalign-
ment, solder joints, and chemical contaminant to crystalline dwell time for complete stress relaxation, which contributes ment, solder joints, and chemical contaminant to crystalline dwell time for complete stress relaxation, which contributes
imperfections. perfections.
The S-N curve is used to interpret the relationship of the stride a mislanding reliability prodiction for surface mount at-The *S-N* curve is used to interpret the relationship of the vide a misleading reliability prediction for surface mount at-
cycle-to-failure and applied stress amplitude from thermal cy-
tachments because accelerated tests tachments because accelerated tests do not closely simulate

The accelerated life test under random vibration stress is usually conducted by elevating the power spectral density (PSD) where N is the mean value of the cycles-to-failure, σ_r is cyclic function of stress, displacement, or acceleration of a product. mal fatigue life: costs. Failures can be due to flaws that vary from gross drilled-hole misalignment, cold solder joints, and chemical $N = \frac{1}{2} \left(\frac{\epsilon_r}{2\epsilon_f} \right)^{\sigma}$ (9) contaminants to crystalline imperfections. For printed circuit board (PCB) level tests, random vibration reduces the ratio of root mean square displacement at the board center to that at where ϵ_r is the strain range, and ϵ_f and *b* are the fatigue duc-
the board edge from 25 with sinusoidal vibration tests to 5.
tility coefficient and exponent. As for material properties. The accelerated random vibr

cases, there is a relation between PSD and fatigue life:

$$
MTTF = C_0 (PSD_R)^{m/2}
$$
 (10)

where MTTF is proportional to cycles to failure, C_0 and m are constants, and PSD_R is the PSD stress value at resonant freconstants, and FSD_R is the FSD stress value at resonant Ire-
quency. From Eq. (10) the acceleration factor for random vi-
bration becomes

$$
AF = \left(\frac{PSD_{R,n}}{PSD_{R,a}}\right)^{m/2} \tag{11}
$$

where PSD_{R,a} and PSD_{R,n} are PSD values at fundamental reso-
nant frequency under accelerated and normal use conditions. Sample moments often are used as estimators of the correnant frequency under accelerated and normal use conditions,

LIFE ESTIMATION FROM TEST DATA

The *life,* or time to failure, of a product (or a component or system in the product) depends heavily on various factors in random nature, such as applied stresses, material properties, where *s* is the estimation of life deviation, and MTTF is estifailure mechanisms, and failure modes. The term "life" may mated from Eqs. $(12-15)$. also represent any suitable measure of exposure, such as the number of thermal or vibration cycles or the number of mis- **Estimation of Confidence Interval of Mean Time to Failure** sions.

failure (MTTF), failure rate, life deviations, and life distribu- following equation: tion. The objective of the life evaluation is to estimate these statistical measures from observed testing data. Because of the random nature of the life data, such an evaluation is usually incomplete due to the limitation of the data sample size. The result of any life calculation is only an estimation of the life at a certain statistical confidence level, to account for the sampling and testing variations.

mation, that is, the ratio of the total component test hours estimation. However, if the time to failure is an exponentially μ (the sum of all the convertion hours on test of all the componentially distributed random v (the sum of all the operation hours on test of all the compo-
nents tested including those that failed) to the number of fail-
nents tested including those that failed) to the number of fail-
nents. For a time-terminated

$$
MTTF = \frac{\sum_{i=1}^{n_f} T_{f,i} + (n - n_f)T_0}{n_f}
$$
(12)

where T_{fi} is the component life hours of the *i*th failed component, *n* is the total number of components tested, n_f is the for time-terminated data with replacement, and by number of failed components, and T_0 is the terminated test time. In time-terminated tests, if a component is replaced as soon as it fails, MTTF is often estimated by

$$
MTTF = \frac{nT_0}{n_f} \tag{13}
$$

S-N curve, because the relationship between input displace- For failure-terminated tests without replacement, assuming ment or acceleration and stress is nonlinear. For some special that the test is terminated at time T_{n_f} when the n_f th failure cases, there is a relation between PSD and fatigue life: has occurred, MTTF can be estimat

$$
MTTF = \frac{\sum_{i=1}^{n_f} T_{f,i} + (n - n_f) T_{n_f}}{n_f}
$$
(14)

$$
MTTF = \frac{nT_{n_f}}{n_f} \tag{15}
$$

respectively. sponding life deviation, which is the expected value of $(T MTTF)^2$ as shown by the following equation for a life test sample of size *n*, namely, T_1, \ldots, T_n :

$$
s = \sqrt{\frac{1}{n-1} \sum_{i=1}^{n} (T_i - \text{MTTF})^2}
$$
 (16)

The life of a product can be described by mean time to The confidence interval of MTTF can be estimated using the

$$
\left\langle \text{MTTF}\right\rangle_{1-\alpha} = \left(\overline{\text{MTTF}} - t_{\alpha/2, n_{\rm f}-1} \frac{s}{\sqrt{n_{\rm f}}}, \overline{\text{MTTF}} + t_{\alpha/2, n_{\rm f}-1} \frac{s}{\sqrt{n_{\rm f}}}\right)_{(17)}
$$

where MTTF is calculated from Eqs. (12-15), $t_{\alpha/2,n-1}$ is the value of Student's *t*-distributed variable corresponding to the confidence level $(1 - \alpha)$, and *s* is the estimate of standard **Estimation of Mean Time to Failure** deviation expressed in Eq. (16).

The common method to estimate MTTF is sample point esti-
mation (17) is a general expression of confidence interval
mation, the time to failure is an exponentially
mation that is the ratio of the total component test hour mined by

$$
\langle \text{MTTF} \rangle_{1-\alpha} = \left(\frac{2n_f \overline{\text{MTTF}}}{\chi^2_{1-\alpha/2, 2n_f+2}}, \frac{2n_f \overline{\text{MTTF}}}{\chi^2_{\alpha/2, 2n_f}} \right) \tag{18}
$$

$$
\langle \text{MTTF} \rangle_{1-\alpha} = \left(\frac{2n_{\text{f}} \overline{\text{MTTF}}}{\chi_{1-\alpha/2, 2n_{\text{f}}}^2}, \frac{2n_{\text{f}} \overline{\text{MTTF}}}{\chi_{\alpha/2, 2n_{\text{f}}}^2} \right) \tag{19}
$$

for failure-terminated data with or without replacement.

The estimation of the lower limit of MTTF, the one-sided **Acceleration Models for Mean Time to Failure** confidence interval of MTTF, can be determined by The acceleration models for MTTF are derived mostly from

$$
\langle \text{MTTF} \rangle_{1-\alpha} = \left(\frac{2n_f \overline{\text{MTTF}}}{\chi_{1-\alpha, 2n_f+2}^2}, \infty \right) \tag{20}
$$
 next.

$$
\langle \text{MTTF} \rangle_{1-\alpha} = \left(\frac{2n_{\text{f}} \overline{\text{MTTF}}}{\chi^2_{1-\alpha, 2n_{\text{f}}}}, \infty \right) \tag{21}
$$

for failure-terminated test data.

mated from life test data. A sample of similar components a material property, then MTTF can be determined by from a hypothesized population of such components is tested under the operational environment. Their times to failure are
recorded. Using t_i as the lifetime to failure of the $n_{f,i}$ th compo-
MTTF = t_0 exp $\left(\frac{E_A}{kT}\right)$ nent, the unreliability or the probability of failure up to time t_i , $F_T(t_i)$, can be estimated by approximating $F_T(t_i)$ as deter- where t_0 is a material constant. mined by

$$
\overline{F}_{\mathrm{T}}(t_i) = \frac{n_{\mathrm{f},i}}{n} \tag{22}
$$

where *n* is the total number of components under test. The reliability at time t_i is then approximately

$$
\overline{R}(t_i) = 1 - \overline{F}_{\text{T}}(t_i) = \frac{n - n_{\text{f},i}}{n}
$$
\n(23)

For a small sample size (say, $n < 15$), the component failure probability at time t_i can be estimated by the following equa-
tion:
ples of quantum mechanics and expresses the time rate of

$$
\overline{F}_{\rm T}(t_i) = \frac{n_{\rm f,i} - 0.3}{n + 0.4} \tag{24}
$$

and the reliability at time t_i is

$$
\overline{R}(t_i) = \frac{n - n_{\text{f},i} + 0.7}{n + 0.4} \tag{25}
$$

The calculated results are often plotted on probability paper to see if the life follows a particular common distribution, $r = r_0 T \exp\left(\frac{r_0 T T}{r_0 T}\right)$ such as a Weibull distribution or log-normal distribution.

LIFE INFERENCE MODELS FOR ACCELERATED TESTING be determined by

The life of a product calculated from the accelerated test data or under normal usage conditions is a random variable. One important task of accelerated life testing is to extrapolate these statistic measures from the test data to the normal us- where t_0 is a material constant. age conditions. This requires life inference models. The models can be categorized into two groups: the acceleration mod- **Peck Model.** The Peck model separately calculates the acels for MTTF and the acceleration models for life distribution. celerations created by temperature and humidity by modi-

empirical tests. The frequently used models are described

Arrhenius Reaction Model. The Arrhenius reaction model expresses the time rate of degradation of some device parame- for time-terminated test data and ter as a function of the operating temperature. According to this model, the reaction rate, *r*, is

$$
r = r_0 \exp\left(-\frac{E_A}{kT}\right) \tag{26}
$$

where r_0 is a constant, E_A is the activation energy for the fail-**Estimation of Life Distribution** stand the stand (8.617 \times 10⁻⁵ eV/K), and *T* is the absolute temperature. In most cases, the cumulative distribution functions are esti- Assuming that the product of the reaction rate and MTTF is

$$
MTTF = t_0 \exp\left(\frac{E_A}{kT}\right) \tag{27}
$$

Power-Law Model. The power-law model is derived via con- F siderations of kinetic theory and activation energy, which gives

$$
MTTF = CS^{-m} \tag{28}
$$

where *C* and *m* are constants and *S* is applied stress. This model has found application for accelerated life tests of paperimpregnated dielectric capacitors and is also used for life modeling of fatigue initiation for most ductile materials.

ples of quantum mechanics and expresses the time rate of degradation of some device parameter, *r*, as function of the ω operating temperature:

$$
r = r_0 T \exp\left(-\frac{E_A}{kT}\right) \tag{29}
$$

 $\overline{R}(t_i) = \frac{n - n_{f,i} + 0.7}{n + 0.4}$ (25) Application of this model can be generalized for a product subjected to two types of stress—a thermally related stress, *T*, and a nonthermally related stress, *S*:

$$
r = r_0 T \exp\left(-\frac{E_A}{kT}\right) \exp\left(CS + \frac{DS}{kT}\right) \tag{30}
$$

where *C* and *D* are constants. Assuming that the product of reaction rate and MTTF is a material property, the MTTF can

$$
MTTF = t_0 \frac{1}{T} \exp\left(\frac{E_A}{kT}\right) \exp\left(CS + \frac{DS}{kT}\right) \tag{31}
$$

$$
MTTF = t_0 \exp\left[\frac{E_A}{k}\left(\frac{1}{T_0} - \frac{1}{T}\right)\left(\frac{RH_0}{RH}\right)^n\right]
$$
(32)

where $n = 2.7$ and $E_A = 0.79$ eV/K.

mostly from the acceleration models for MTTF and the com-
more level or, equivalently, that the natural logarithm of the life
more life distributions. The frequently used models are do has a normal distribution. The stand mon life distributions. The frequently used models are described next.

Arrhenius–Exponential Model. This model assumes that the bution function is product life has an exponential distribution at a given stress level, and the natural logarithm of the MTTF is an inverse function:

$$
\ln(MTTF) = C_1 + \frac{C_2}{S}
$$
 (33)

where S is the applied accelerated stress, and C_1 and C_2 are
constants determined from the test data. Therefore the cumu-
lative distribution function is
dence of life on accelerated stress. The model assumes that

$$
F_{\rm T}(t,S) = 1 - \exp\left[-t \exp\left(C_1 + \frac{C_2}{S}\right)\right]
$$

bution at a given stress level or, equivalently, that the natural logarithm of the life has a normal distribution. The standard deviation, σ_{t} , of the logarithm of life is a constant; and the logarithm of the MTTF is an inverse function of *S*. Therefore the cumulative distribution function is More complicated models can be derived with other assump-

$$
F_{\rm T}(t,S) = \Phi\left(\frac{\log t - \mu_{\rm T}(S)}{\sigma_{\rm T}}\right) \tag{34}
$$

tion, and $\mu_T(S)$ is the mean of logarithm of life. time t_{i-1} , and runs to time $t_i(t_0 = 0)$, and the cumulative distri-

combines a Weibull life distribution with an Arrhenius dependence of life on accelerated stress. The model assumes that *f*_{the product life has a Weibull distribution at a given stress} level, and that the shape parameter β is a constant (independent of applied accelerated stress). The natural algorithm of
the equivalent start time τ_1 for step 2 would have produced
the characteristic life, η , i of of *S*:

$$
\ln\eta=C_1+\frac{C_2}{S}\qquad \qquad (35)
$$

Therefore the cumulative distribution function is time *t* is

$$
F_{\rm T}(t,S) = 1 - \exp\left\{-\left[t\exp\left(C_1 + \frac{C_2}{S}\right)\right]^\beta\right\} \tag{36}
$$

Power–Exponential Model. The power–exponential model F_1 assumes that the product life has an exponential distribution

fying the Arrhenius and Eyring models: at any given stress level, and that the MTTF is a power law function of accelerated stress, *S*. Therefore the cumulative distribution function is

$$
F_{\rm T}(t,S) = 1 - \exp\left(-\frac{S^m t}{C}\right) \tag{37}
$$

Acceleration Models for Life Distribution Power–Log-Normal Model. This model assumes that the The acceleration models for life distribution are derived product life has a log-normal distribution at any given stress meetly from the acceleration models for MTTF and the acceleration equivalently, that the natural loga function of accelerated stress, *S*. Then the cumulative distri-

$$
F_{\rm T}(t,S) = \Phi\left(\frac{\log t - CS^{-m}}{\sigma_{\rm T}}\right) \tag{38}
$$

where Φ is the standard normal cumulative distribution function.

the product has a Weibull distribution at a given stress level, and that the shape parameter β is a constant (independent on applied accelerated stress). The characteristic life, η , is a **Arrhenius–Log-Normal Model.** The Arrhenius–log-normal (28). Therefore the cumulative distribution function is model assumes that the product life has a log-normal distri-

$$
F_{\rm T}(t,S) = 1 - \exp\left[-\left(\frac{tS^m}{C}\right)^\beta\right]
$$
(39)

tions substituted in the life distribution and accelerated $MTTF$ _{models}.

Step Stress Model. The step stress model can be explained where Φ is the standard normal cumulative distribution func- as follows. Suppose that step *i* runs at stress S_i , starts at bution function (CDF) of time to failure for specimens run at **Arrhenius–Weibull Model.** The Arrhenius–Weibull model a particular stress level S_i is denoted by $F_i(t)$. Therefore, for mbines a Weibull life distribution with an Arrhenius depen-step 1, we have

$$
F(t) = F_1(t_1) \qquad 0 \le t \le t_1 \tag{40}
$$

$$
F_2(\tau_1) = F_1(t_1) \tag{41}
$$

The cumulative fraction of specimens failing in step 2 by total

$$
F(t) = F_2[(t - t_1) + \tau_1] \qquad t_1 \le t \le t_2 \tag{42}
$$

Similarly, in step 3 the equivalent start time τ_2 is the solution of

$$
F_3(\tau_2) = F_2[(t_2 - t_1) + \tau_1]
$$
\n(43)

total time *t* is may occur, and their effect and criticality on the operation

$$
F(t) = F_3[(t - t_2) + \tau_2] \quad t_2 \le t \le t_3 \tag{44}
$$

the predominant mechanical, thermal, electrical, chemical, thermal, electrical, chemical,

$$
F_i(\tau_{i-1}) = F_{i-1}[(t_{i-1} - t_{i-2}) + \tau_{i-1}]
$$
\n(45)

$$
F(t) = Fi[(t - ti-1) + \taui-1] \quad ti-1 \le t \le ti
$$
 (46)

As an example, let us assume that the life distribution at any cycle mission profile. The accelerated stress may produce failure mechanisms stress level is Weibull:

$$
F_i(t) = 1 - \exp\left[-\left(\frac{t}{\theta}\right)^{\beta}\right]
$$
 (47)

$$
\theta = \theta_{\rm o} \left(\frac{S_{\rm o}}{S} \right)^C \tag{48}
$$

operational stress condition. Therefore the distribution of

$$
F(t) = 1 - \exp\left\{-\left[\left(\frac{t - t_{i-1} + \tau_{i-1}}{\theta_0}\right)\left(\frac{S_i}{S_0}\right)^C\right]^\beta\right\} \tag{49}
$$

$$
\tau_{i-1} = (t_{i-1} - t_{i-2} + \tau_{i-2}) \left(\frac{S_{i-1}}{S_i}\right)^{\!C} \tag{50}
$$

Thus the time to failure distribution under the step stress pattern consists of segments of a Weibull distribution.

FAILURE MECHANISMS ANALYSIS

Failure is the loss of the ability of a product to perform a required function. This definition includes catastrophic failures as well as degradation failures, whereby an important parameter drifts significantly to cause improper functioning. Failures of an electronic product can be classified by the failure site, the failure mechanism, and the failure mode. Failure site is the location or unit where failure occurs. The failure mechanism is the process by which the specific combination of physical, electrical, chemical, and mechanical stresses induces failure. Failure mode is a physically observable change caused by the failure mechanism, such as an open-circuit, a short-circuit, or a change in parameters.

A correct failure analysis in accelerated life tests should begin with an investigation of all potential failure mecha-

and the cumulative fraction of specimens failing in step 3 by nisms, followed by an identification of where and when they of the product over the required useful life. In order to most *F*_{*k*} $f(x) = f(x)$ and $f(x$ given failure mechanism can occur at many sites, failures In general, the equivalent start time of step i , t_{i-1} , is the solu- must be identified with respect to the failure mechanisms and and radiation stresses which induce failure (see Table 2). The *failure mechanisms should not be mixed with failure modes* or defects, which serve as sources of failure. Investigations of and the CDF for step stress testing is given by failure mechanisms serve as pointers for design of reliability testing. It is therefore necessary to first identify the failure *F*(*n*) mechanisms that could potentially be activated in an electronic product by the applied stresses, resulting from the life

that are different from those observed during actual service conditions. Therefore failure mechanism identification and the setting up of stress limits for all types of accelerated life tests in order to prevent shifting of the original dominant failure mechanism are necessary. If failure mechanism shifting where the shape parameter β is a constant, and the scale pa-
raneter θ is a function of applied stress level:
resentative of the reliability under actual operating condiresentative of the reliability under actual operating conditions and the test would not be a valid acceleration.

In the planning of an accelerated life test, an understanding of the change in interference pattern of various failure mechanisms as well as the acceleration stresses is critical. The subscript o in the above equation denotes the state of The selection of the proper accelerated stress should be based operational stress condition. Therefore the distribution of on the identification of failure mechani time to failure is should be conducted to validate the results of accelerated tests and correct the cause of failure.

A successful accelerated testing should meet the following conditions: (1) the failure mechanisms in the accelerated environment are the same as those observed under usage conditions; (2) the material properties under accelerated stress are where t_{i-1} is the solution of the following equation: not changed; (3) the shape of the failure probability density function at normal operating levels and accelerated conditions should be consistent; and (4) the quantitative extrapolation from the accelerated environment to the usage en-

Table 2. Failure Mechanisms and Accelerated Stresses

Wear-out Failure Mechanisms	Acceleration Stresses		
Fatigue crack initiation	Mechanical stress/strain range, cyclic		
Fatigue crack propagation	temperature range, frequency Mechanical stress range, cyclic temper- ature range, frequency		
Creep	Mechanical stress, temperature		
Wear	Contact force, relative sliding velocity		
Diffusion	Temperature, concentration gradient		
Interdiffusion	Temperature		
Corrosion	Temperature, relative humidity		
Electromigration	Current density, temperature, temper- ature gradient		
Dendritic growth	Voltage differential		
Radiation damage	Intensity of radiation		
Surface charge spreading	Temperature		
Slow trapping	Temperature		
Stress corrosion	Mechanical stress, temperature, rela-		
	tive humidity		

vironment must be made with some reasonable degree of **LIFTOFF OF EPITAXIAL FILM.** See EPITAXIAL LIFTOFF. confidence.

Accelerated life testing may produce significant costs for many types of equipment or sytems. To keep both costs and the uncertainties under control, accelerated life testing should be carried out in a systematic way, using all the available knowledge in the testing planning.

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